



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Attn: OIPE

Satoshi INOUE, et al.

Application No.: 10/748,206

Docket No.: 040852.98

Filed: December 31, 2003

For: MANUFACTURING METHOD OF ACTIVE MATRIX SUBSTRATE, ACTIVE
MATRIX SUBSTRATE AND LIQUID CRYSTAL DISPLAY

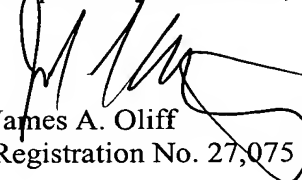
REQUEST FOR CORRECTION OF PALM RECORDS

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Sir:

Attached is a photocopy of the original filing receipt on which an error has been corrected in red. This error are being brought to the attention of the Patent and Trademark Office so that it may correct its records.

Respectfully submitted,



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Date: March 22, 2004

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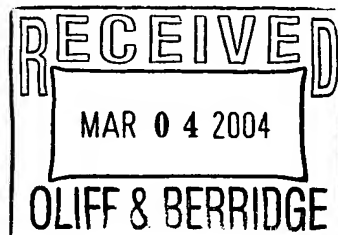
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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/748,206	12/31/2003	2812	770	040852.98	27	7	1

 25944
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CONFIRMATION NO. 5363

FILING RECEIPT



OC000000011972042

Date Mailed: 02/26/2004

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Applicant(s)

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Suwa-shi

Domestic Priority data as claimed by applicant

 This application is a DIV of 10/263,070 10/03/2002
 which is a REI of 09/113,373 07/10/1998 PAT 6,127,199
 which is a CIP of PCT/JP97/04110 11/11/1997

Foreign Applications

 JAPAN 8-315590 11/12/1996
 JAPAN 8-327688 11/22/1996

Projected Publication Date: None, application is not eligible for pre-grant publication

Non-Publication Request: No

Early Publication Request: No

Title

Manufacturing method of active matrix substrate, active matrix substrate and liquid crystal display

device

Preliminary Class

438

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